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EXPOSURE APPARATUS



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ABSTRACT

The exposure apparatus has an illumination optical system equipped with an illuminance-uniformity unit (3A) composed of a diffusion plate (31), a conical prism (32), a reflecting member (34) in a columnar form, a reflecting member (33) in a cylindrical form, a fly-eye lens (35) and a stop (36). The exposure apparatus is for use in a lithography process for manufacturing semiconductors and so on. The illumination light from an optical system of a previous stage has an illuminance distributed in a uniform manner to some extent by multiple reflection between the reflecting plane of the reflecting member (34) and the reflecting plane of the reflecting member (33) via the diffusion plate (31) and the conical prism (32), and the illumination light is then led to a reticle at a high degree of illuminance through the fly-eye lens (35) and the stop (36).